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# Design of Bulk Thermoelectric Modules for Integrated Circuit Thermal Management

Kazuhiko Fukutani and Ali Shakouri

**Abstract**—Various parameters affecting the performance of bulk thermoelectric (TE) modules used for integrated circuit (IC) thermal management are studied. An effective circuit model is developed that takes into account various ideal and nonideal effects in the module. It is shown that there is an optimum module thickness and an optimum operating current which depend on the overall heat dissipation and on the external thermal resistances. Optimized TE modules with  $ZT \sim 0.8$ , will have a cross section over leg length ratio of 0.037 m, can increase the chip operation power by 15% in comparison with the case without a TE cooler while maintaining the chip temperature below 100 °C. This is for a package thermal resistance of 0.2 K/W. Prospects for TE material with higher  $ZT$  values and the effect of contact resistance on the power dissipation density are also discussed. The results presented in this paper can be used in applications other than in the IC thermal management when external thermal resistances dominate the performance of TE modules.

**Index Terms**—Contact resistance, equivalent circuit models, external thermal resistance, integrated circuit (IC), thermal management, thermoelectric (TE) modules.

## I. INTRODUCTION

CONTROLLING the operating temperature of microelectronic devices has become more important in recent years because heat generated by the devices has increased substantially due to device miniaturization and increased switching speeds. Recently, most integrated very large scale integrated (VLSI) circuits are designed with cooling systems to further increase clock speeds. Among the various cooling systems, thermoelectric coolers (TECs) have a lot of advantages compared with nonrefrigeration systems. For example, TECs can reduce the operating temperature of electric devices below the ambient temperature, or the temperature could be reduced compared to passive systems in some cases; additionally they are compact, quiet, and have no moving parts. However, a TEC's performance is not always superior to that of nonrefrigeration systems, such as a cooling fan or natural convection, because TECs need to dissipate the pumped heat as well as the Joule heat generated by the operating current at the hot end, which sometimes degrades the overall system performance. Therefore, it is very important to design a TEC to be effective.

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Previously, Phelan *et al.*, Simons *et al.*, and Solbrekken *et al.* predicted the performance of a conventional bulk BiTe-based TEC in an electronic package environment [1]–[5]. In Phelan's paper [1], they assumed the optimum operating current  $I_{\text{opt}}$  to be  $I_{\text{opt}} = \alpha T_c G / \rho$ , where a  $\alpha$  is the Seebeck coefficient,  $T_c$  is the cold side temperature,  $\rho$  is the electrical resistivity of the TE element, and  $G$  is a geometrical factor equal to the cross-sectional area divided by the leg length of each element in a couple. This assumption is valid if the value of the thermal resistance between the hot end of the TEC and the ambient air ( $R_2$ ) can be neglected compared with the value of the thermal resistance of TEC ( $R_{th}$ ). However,  $R_2$  can't be neglected in most cases and a new optimum current should be calculated [2], [3], [5]. This will have significant impact on TEC's performance to reduce the operating chip temperature ( $T_{\text{chip}}$ ) for a given power dissipation [2], [3], [5]. Also, although it is basically difficult to change the TE material properties, the geometrical factor ( $G$ ) can be easily changed to maximize the TEC performance from the viewpoint of the system design. Therefore, if the operating current and TEC geometry are optimized at the same time by taking into account the external thermal resistance such as  $R_2$ , it will increase the TEC's potential furthermore.

In this paper, we extend the previous work and predict the cooling performance of the conventional bulk TEC integrated with an integrated circuit (IC) chip and heat sink. In order to maximize the TEC performance in a package environment, the operating current and TEC geometry factor ( $G$ ) are optimized to minimize the chip temperature by taking into account the external thermal resistance. An one-dimensional (1-D) electrothermal model was developed to conduct numerical studies for a simple estimation. At the beginning, the improvement of the TEC performance by optimizing the operating current as well as by modifying TEC geometry will be discussed. Finally, the effect of material properties and contact resistance on a power dissipation density in various package environments will also be discussed.

## II. DEVICE MODELING

Fig. 1(a) and (b) illustrate a schematic representation of a chip with and without a TEC. In both situations, the heat generated by a chip flows through a chip, (TEC module) and heat sink to the ambient air. In the case with the TEC shown in Fig. 1(a), some heat is electrically pumped from the cold side to the hot side of the TEC based on the Peltier effect. Meanwhile, there is Joule heating generated inside the TEC due to the operating current and electrical resistance.

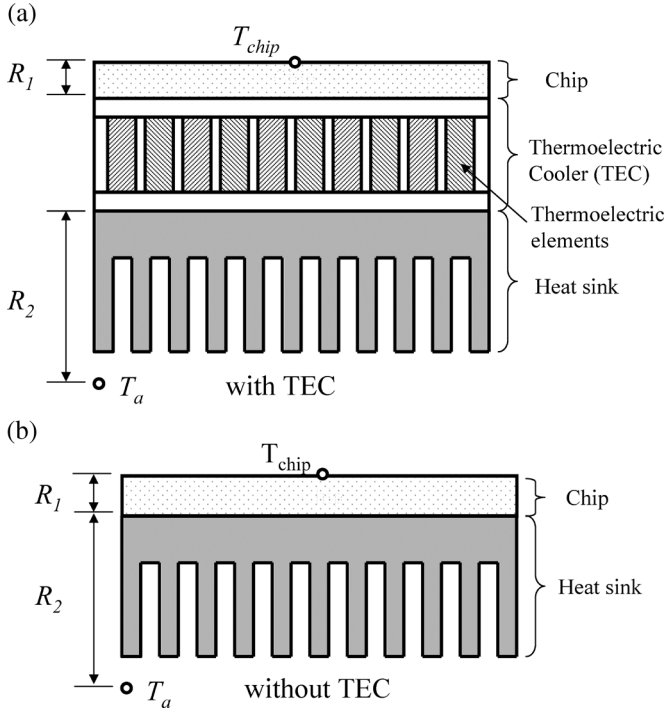


Fig. 1. Schematic representation of a chip (a) with and (b) without a TEC. The external thermal resistances (shown as  $R_1$  and  $R_2$ ) are described for the chip and hot side of TEC to ambient.

Fig. 2(a) and (b) show the equivalent circuit device models of chips with and without a TEC. Resistors represent thermal resistances. Here, Peltier cooling and heating and Joule heating are modeled with current sources. There are two Peltier effects and one Joule heating in the model with a TEC shown in Fig. 2(a). The two Peltier effects include Peltier cooling at the cold side of the TEC ( $Q_c$ ) and Peltier heating at the hot side of the TEC ( $Q_h$ ). It is simple to show that one can always put the Joule heating current source ( $Q_j$ ) in the middle of the TEC thermal resistance ( $R_{th}$ ) regardless of the thermal boundary conditions at the two ends [6]. Furthermore, in the case of the model with the TEC,  $R_1$  is the sum of the thermal resistance of the chip substrate and the interface thermal resistance between the chip and the cold side of the TEC, and  $R_2$  is the sum of the interface thermal resistance between the hot end of the TEC and the heat sink and the thermal resistance of the heat sink to ambient air, indicating external thermal resistances.  $Q_j$  is given by  $2NI^2R_e$ , where  $N$  is the number of couples in the TEC,  $I$  is the operating current, and  $R_e = \rho/G$  is the electrical resistance of the TEC.  $G = S/L$  is a geometrical factor described by the ratio of the leg's cross-sectional area ( $S$ ) to its length ( $L$ ), and  $\rho$  is the electrical resistivity of the TE element, which is assumed to be equal for the  $n$ -type and  $p$ -type elements.  $Q_{c,h}$  can be described by the equation  $Q_{c,h} = 2N\alpha IT_{c,h}$ , where  $T_c$  is the cold side temperature of the TEC and  $T_h$  is the hot side temperature of the TEC.  $R_{th}$  can be described by the equation  $R_{th} = 1/2NkG$ , where  $k$  is the thermal conductivity of the TE elements, which is also assumed to be equal for the  $n$ -type and  $p$ -type elements.  $T_a$  is a constant voltage source modeling the ambient temperature and  $T_{chip}$  is the actual operating temperature of the chip. In the model with the TEC, if heat that flows from the chip ( $Q$ ) and the operating current ( $I$ ) are given, we can easily

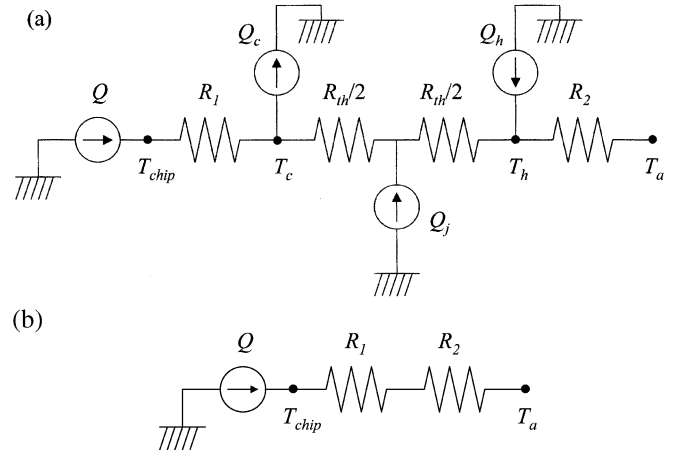


Fig. 2. Equivalent circuit device model for a chip (a) with and (b) without a TEC.

calculate  $T_{chip}$ ,  $T_c$ , and  $T_h$  by using Kirchoff laws from the circuit model.

In order to compare our calculation results with Phelan's results, we used the same TEC design based on a commercially available TEC from Melcor, Model CP5-31-061 [1]. According to the data sheet published by Melcor [7], the device geometry is  $55 \times 55 \times 4.9$  mm, the maximum heat-pumping rate ( $Q_{max}$ ) is 125 W, and the maximum cooling temperature difference ( $\Delta T$ ) is  $67^\circ\text{C}$  at the hot side temperature of  $25^\circ\text{C}$ . The parameters used for the calculation are  $N = 31$ ,  $G = 0.01196$  m,  $k = 1.5$  W/mK,  $\rho = 10^{-5}$   $\Omega\text{m}$ ,  $\alpha = 2 \times 10^{-4}$  V/K. In all calculations, the ambient temperature ( $T_a$ ) is assumed to be  $25^\circ\text{C}$ . To evaluate the effectiveness of a TEC,  $T_{chip}$  for no TEC system was also calculated assuming the same value of  $R_1$  and  $R_2$  as the TEC system by using the equivalent circuit model shown in Fig. 2(b). The temperature dependence of material properties is not taken into account in this calculation for the simplicity.

### III. RESULTS AND DISCUSSION

In order to calculate the relationship between the heat dissipation ( $Q$ ) and the chip temperature ( $T_{chip}$ ), the value of  $R_1$  and  $R_2$  must be determined. To compare our results with Phelan's calculation, the same value was assumed for  $R_1$  and  $R_2$ ;  $R_1 = 0.571$  K/W,  $R_2 = 0.049$  K/W [1]. For these conditions, the results of the two calculations are compared in Fig. 3(a). This figure shows the relationships between dissipated power,  $Q$ , (or  $q$ : heat dissipation density) and the chip temperature,  $T_{chip}$ , calculated by the different models. In this figure, one plot is calculated by using Phelan's model and another plot is calculated from the equivalent circuit model. Here,  $q$  is calculated by assuming the TEC area of the TEC is  $5.5 \times 5.5$   $\text{cm}^2$ . For reference, the result with no TEC is also shown in the same graph. In our calculation,  $I$  was determined to minimize  $T_{chip}$ , indicating that  $I$  is optimized by considering the value of  $R_2$ . There is little difference between Phelan's results and ours. This is attributed to the small value of  $R_2$  compared with the thermal resistance of the TEC ( $R_{th}$ ). In our model, the optimum current ( $I_{opt}$ ) that can minimize  $T_{chip}$  is expressed by

$$I_{opt} = \frac{\alpha(R_{th}T_c - \Delta TR_2)}{R_e(R_{th} + 2R_2)} \quad (1)$$

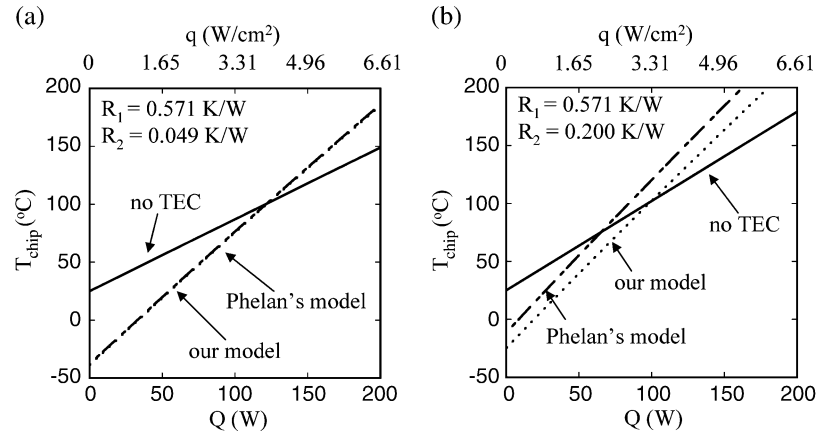


Fig. 3. Relations between the chip operating temperature ( $T_{\text{chip}}$ ) and the heat dissipation ( $Q$ ) or the heat dissipation density ( $q$ ) calculated by the different models are shown for (a)  $R_2 = 0.049$  K/W and (b)  $R_2 = 0.2$  K/W. The no TEC case is also shown as a solid line. Since the TEC is  $5.5 \times 5.5$  cm<sup>2</sup>,  $Q$  axis could be translated to heat power density ( $q$ ) in W/cm<sup>2</sup> removed from the chip.

where  $\Delta T$  is a temperature difference between the hot side and cold side of TEC, defined by  $T_h - T_c$ . If  $R_{th} \gg R_2$  in the (1),  $I_{\text{opt}}$  is given by  $I_{\text{opt}} \approx \alpha T_c G / \rho$ , which is consistent with the optimum current for Phelan's model. At above calculation condition,  $R_{th} = 0.899$  W/K and  $R_2 = 0.049$  K/W are used, which means that  $R_{th} \gg R_2$ . Therefore, our calculation result should be almost the same as the Phelan's calculation result.

Furthermore, as Phelan *et al.* noted previously, it can be seen that the TEC can be effective and cool the chip only when  $Q < Q_{\text{max}} = 125$  W, suggesting that the TEC is not always superior to that of nonrefrigeration systems. In other words, the TEC is beneficial if it is used below its maximum capacity in this condition.

Other important advantages offered by the TEC can also be seen from this figure. The minimum  $T_{\text{chip}}$  without a TEC is the ambient temperature, however, the minimum  $T_{\text{chip}}$  with a TEC is around  $-40$  °C at  $Q = 0$ . This result indicates that the TEC can reduce the chip temperature below the ambient temperature, which is impossible for non-refrigeration systems.

Generally, the value of  $R_2$  strongly depends on the heat sink. When we consider the total cost of the TE system, we might use a heat sink with a higher  $R_2$  to reduce the cost. In order to investigate the effects of  $R_2$  on the cooling performance, we changed the value of  $R_2$  from 0.049 to 0.2 K/W, a value that is approximately the same level as typical thermal resistance of ArctiCoolers [8]. Fig. 3(b) shows the results for  $R_2 = 0.2$  K/W, while keeping other calculation parameters same with the calculation in Fig. 3(a). A big difference between Phelan's calculation and ours is observed. It can be seen that the TEC calculated by our model exhibited at least 10 °C temperature reductions, compared with  $T_{\text{chip}}$  for the TEC calculated by Phelan's model in all cases. This result indicates that the current optimization taking into account  $R_2$  provides significant effect to enhance the TEC potential. Solbrekken *et al.* reached a similar conclusion in [2], [3]. Furthermore, we can see that when  $Q \approx 100$  W  $T_{\text{chip}}$  calculated by our model corresponds to that of no TEC, which is different from Fig. 3(a). This result indicates that the range of  $Q$  where the performance of TEC is better than that of no TEC becomes smaller as the value of  $R_2$  is increased. Therefore, it can be said that the value of  $R_2$  is a very important factor that can determine the performance of a TEC.

The geometrical factor ( $G$ ) is another parameter influencing the TEC's performance because it changes the value of  $R_e$  and  $R_{th}$ . In our paper, the TEC geometry factor ( $G$ ) is defined by the equation  $G = S/L$ , where  $S$  is the TE element's cross-sectional area and  $L$  is its leg length. In order to further improve the performance of the TEC,  $G$  and  $I$  were optimized at the same time without changing other parameters. A comparison of the results with and without TEC is shown in Fig. 4(a) for  $R_1 = 0.571$  K/W and  $R_2 = 0.2$  W/K. In the calculation for the case with TEC, the  $G$  and  $I$  were determined to minimize  $T_{\text{chip}}$  at a given  $Q$  (or  $q$ ).  $q$  is also calculated by assuming the device area of the TEC is  $5.5 \times 5.5$  cm<sup>2</sup>. A great improvement is observed from this figure. Optimized TE modules calculated by our model can increase the heat dissipation power  $Q$  by at least 15% in comparison with the case without TEC while maintaining the chip temperature below 100 °C. Furthermore, one can see that  $T_{\text{chip}}$  for the TEC is always lower than that for no TEC in the entire range of this calculation for all  $Q$ . The results show that  $G$  optimization of the TE elements is also very useful to decrease the chip operating temperature if the heat flow rate generated by the chip can be determined.

Fig. 4(b) shows the value of the optimized  $G$  calculated for different levels of heat dissipation. It can be seen that the optimized  $G$  increases as  $Q$  increases. This result indicates that the optimum TEC leg length ( $L_{\text{opt}}$ ) is thinner as the chip power increases, assuming a constant cross-sectional area of the elements. Therefore, it can be said that there is an optimum leg length that gives the highest heat dissipation density to the IC chip and further thinning or thickening of its length degrades the TEC cooling performance. For example, at  $Q = 100$  W, assuming the cross-sectional area of an element is  $5 \times 5$  mm<sup>2</sup> (or  $2 \times 2$  mm<sup>2</sup>), the optimum length of each element becomes approximately 769  $\mu\text{m}$  (or 123  $\mu\text{m}$ ), which is thinner than the leg thickness of a commercially available TEC (2–3 mm).

It was previously noted that  $R_2$  is an important factor influencing the device performance although the value of  $R_1$  was not critical [1]. Fig. 5 shows the relationships between  $R_2$  and  $T_{\text{chip}}$  for a constant  $Q = 100$  W with and without a TEC. The optimized  $I$  and  $G$  were used for this calculation. For the purpose of comparison, the result calculated by the Phelan's model (without the optimization of  $G$  and  $I$  considering  $R_2$ ) is shown

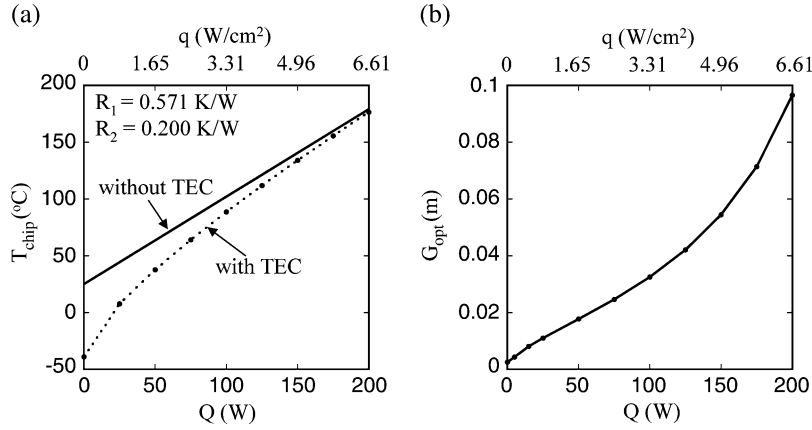


Fig. 4. (a) Relationship between  $T_{\text{chip}}$  and  $Q$  (or  $q$ ) calculated by using optimized  $G$  and  $I$  is shown for  $R_1 = 0.571$  K/W and  $R_2 = 0.2$  K/W. The result for no TEC is also shown as a solid line. (b) The optimized  $G$  for different levels of  $Q$  is shown. Here,  $G$  is a geometrical factor equal to the cross-sectional area ( $S$ ) divided by the leg length of each element ( $L$ ) in a couple.

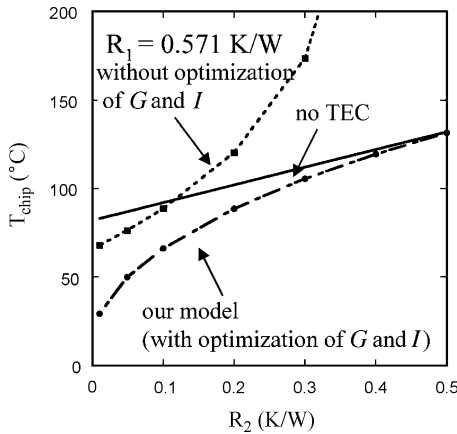


Fig. 5. Relationship between  $R_2$  and  $T_{\text{chip}}$  for a constant  $Q = 100$  W with and without a TEC are shown. The result calculated without the optimization of  $G$  and  $I$  is also shown as a dotted line.

as a dotted line. In this calculation range, optimally designed TEC is able to lower the chip temperature compared to the no TEC case in the entire range although the effectiveness of TEC is reduced as  $R_2$  increases. At high values of  $R_2$  heat generated by TEC can't be sufficiently dissipated to ambient air and thus TEC does not give any improvement. On the other hand, if  $G$  and  $I$  are not optimized,  $T_{\text{chip}}$  increases exponentially with  $R_2$ . Therefore, it can be said that this optimization method is very effective to increase the TEC potential at various external thermal resistances.

We have discussed the way to improve device performance without changing material parameters so far. Generally, the material property is expressed by using the figure of merit  $Z$ , which can be described by the equation  $Z = \alpha^2/\rho k$  [9]. Recently, a new way to improve the material property was proposed by using low dimensional structures, thermionic emission and by reducing phonon transport [10]–[13]. For example,  $ZT = 2.4$  was achieved with the  $\text{Bi}_2\text{Te}_3$  superlattice structure by Venkatasubramanian *et al.* [12]. Harman *et al.* demonstrated the  $\text{PbSeTe/PbTe}$  quantum dot superlattice with  $ZT = 1.6$  [13]. Additionally, there is no physical limitation on how large  $ZT$  could

be for a material. Therefore, the  $ZT$  for commercial devices is expected to reach 2 or 3 in the near future. Fig. 6(a) shows the results for various  $ZT$  values with and without TEC for  $R_1 = 0.571$  K/W and  $R_2 = 0.2$  K/W. As shown in the equation of  $Z$ , it is possible to change  $Z$  by controlling three material properties:  $\alpha$ ,  $\rho$ , and  $k$ . Even though Simmons *et al.* [5] claimed that  $\alpha$  is a more important factor to improve maximum cooling performance of TEC module in a packaged system, we found that improving  $Z$  by each of the three parameters has approximately the same effect when TEC is used to cool the whole chip. This is due to full optimization of both TEC operating current  $I$  and its geometry factor  $G$  to minimize  $T_{\text{chip}}$ . Therefore,  $Z$  is improved by changing  $\alpha$  in this calculation. All other material parameters such as  $k$  and  $\rho$  are unchanged. On the other hand, in cases when the TE element is used for hot spot removal directly on the chip, we have shown that  $Z$  is not the main parameter determining the maximum cooling. In these particular applications, Seebeck coefficient plays a more important role due to 3-D heat and current spreading [14], [15].

In this calculation,  $G$  and  $I$  for TEC case are also optimized to minimize  $T_{\text{chip}}$ . It can be seen that the performance of TEC can be improved dramatically as  $ZT$  increases. At  $Q = 100$  W, the difference of  $T_{\text{chip}}$  between the value of  $ZT = 3$  and no TEC reaches about 70 °C. This result indicates that the TEC will be a more beneficial technique to cool the chip compared with other cooling technology at higher  $ZT$  values. From these results, we can conclude that the device design which takes account of  $R_2$  as well as the improvement of material properties is key factor to increase the TEC's potential in IC chip thermal management.

Fig. 6(b) shows the optimum current and consumed power as a function of  $Q$  at various  $ZT$ s. The optimum current increases with an increase of  $Q$  at any  $ZT$ s. One may point out that the value of the optimum current at higher  $Q$  is quite large to drive the TEC. However, it should be noted that the operating current of TEC module could be reduced (at the expense of higher voltages) by using larger number of elements and smaller cross section for each element but keeping the cooling power the same. Meanwhile, the consumed power of all the plots saturates at some point, and decreases especially in case of the plot for  $ZT = 0.8$ . This is due to a reduction of the TEC's electrical

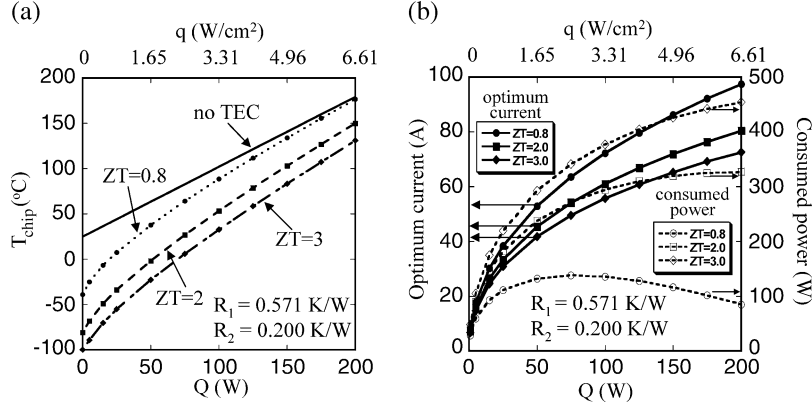


Fig. 6. (a) Relationship between  $T_{\text{chip}}$  and  $Q$  (or  $q$ ) is shown for the various  $ZT$ s with and without a TEC for  $R_1 = 0.571$  K/W and  $R_2 = 0.2$  K/W. The result for no TEC is also shown as a solid line. (b) The optimum current for maximum cooling and consumed power as a function of  $Q$  at various  $ZT$ s.

resistance ( $R_e$ ) because an optimum  $G$ , which changes  $R_e$ , increases with an increase of  $Q$ . Both of the optimum current and consumed power increase when the  $ZT$  is larger, indicating that there is a tradeoff between lower  $T_{\text{chip}}$  achievement and consumed power.

Until now, we basically discussed the heat dissipation of the TEC module ( $Q$  in  $W$ ) instead of the heat dissipation density ( $q$  in  $W/\text{cm}^2$ ). As we mentioned previously, if the TEC area is fixed,  $q$  can be calculated from the geometry. For example, assuming the device geometry of the TEC is  $5.5 \times 5.5$  cm<sup>2</sup>,  $Q$  of 100  $W$  could be translated to heat power density ( $q$ ) of 3.31  $W/\text{cm}^2$  removed from the chip. However, we can use any combination of the cross-sectional area ( $S$ ) and leg length of the TE elements ( $L$ ) at the constant  $G = S/L$ , suggesting the maximum cooling capacity itself may be changed even if  $G$  is constant.

The analytical solution for the cooling capacity of the TEC obtained from the circuit model in the package environment, can be expressed by

$$Q = \frac{2NI\alpha(T_c R_{th} - \Delta T R_2) - NI^2 R_e (R_{th} + 2R_2) - (T_a - T_c)}{(R_{th} + R_2)} \quad (2)$$

where  $T_c = T_{\text{chip}} - QR_1$ . The external unit thermal resistances ( $R_{1,2}^*$ ) of the package are given by the equation  $R_{1,2}^* = R_{1,2}A$  where  $A$  is the area of contact and  $R_{1,2}$  is the external thermal resistance [1]. If we assume that the area of the TE elements ( $2NS$ ) is a half of the total area of the TEC (50% coverage), and that  $R_1$  and  $R_2$  are inversely proportional to the total area of the TEC, the heat dissipation density of the TEC in the package environment can be given by

$$q = \frac{Q}{2 \cdot 2NS} = \frac{I^* \alpha \left( T_c \frac{L}{k} - \Delta T \frac{R_2^*}{2} \right) - I^{*2} \cdot \frac{\rho L}{2} \left( \frac{L}{k} + \frac{2R_2^*}{2} \right) - (T_a - T_c)}{2 \left( \frac{L}{k} + \frac{R_2^*}{2} \right)} \quad (3)$$

where  $T_c = T_{\text{chip}} - qR_1^*$ ,  $I^*$  is a current density given by the equation  $I^* = I/S$ ,  $R_1^*$  is the unit thermal resistance between the IC chip and the cold side of TEC described by the  $R_1^* =$

$R_1 \times 4NS$  and  $R_2^*$  is the unit thermal resistance between the hot side of TEC and ambient described by the  $R_2^* = R_2 \times 4NS$ . From the (3), one can understand that the heat dissipation density ( $q$ ) is independent of  $N$  and  $S$ . In other words,  $q$  is only dependent of  $L$  and  $I^*$  when the material properties and unit thermal resistance are given. Therefore, if the total area of the TE elements ( $2NS$ ) is changed by increasing  $S$ , it induces only the decrease of  $I^*$ .

Generally, the chip operating temperature has to be less than 100 °C to avoid significant degradation due to electromigration or oxide breakdown. Therefore, the maximum heat dissipation density at  $T_{\text{chip}} = 100$  °C ( $q_{\text{max}}$ ) was calculated as a function of  $R_2^*$  and  $ZT$ .  $R_1^*$  at  $R_1 = 0.571$  K/W and  $R_2^*$  at  $R_2 = 0.2$  K/W are estimated to be  $1.73 \times 10^{-3}$  and  $6.05 \times 10^{-4}$  m<sup>2</sup>K/W, respectively, assuming  $A$  is  $5.5 \times 5.5$  cm<sup>2</sup> (the area of TEC module). In real configuration, the contact area of the IC chip could be different from the total area of TEC module, and a spreading resistance should be introduced.

Fig. 7(a) shows a contour plot of  $q_{\text{max}}$  as a function of  $R_2^*$  and  $ZT$ . We fixed  $R_1^* = 1.73 \times 10^{-3}$  m<sup>2</sup>K/W and other device and material parameters except for  $\alpha$  and  $L$  in our calculation, and then found  $q_{\text{max}}$  for each value of  $R_2^*$  and  $ZT$ . In this calculation  $L$  and  $I^*$  are also optimized to minimize  $T_{\text{chip}}$ . For the purpose of comparison,  $q_{\text{max}}$  calculated from no TEC case is shown on the top of graph. From Fig. 7(a), we can clearly see that  $q_{\text{max}}$  is maximized at high  $ZT$  and low  $R_2^*$ . When  $R_2^*$  is reduced from  $6.05 \times 10^{-4}$  (current technology value) to  $1.61 \times 10^{-4}$  m<sup>2</sup>K/W (a factor of 3.75), the value of  $q_{\text{max}}$  is changed from 3.70 to 5.44  $W/\text{cm}^2$  at  $ZT = 0.8$ ; nearly a factor of 1.47 higher. Meanwhile, the value of  $q_{\text{max}}$  is changed from 3.70 to 5.52  $W/\text{cm}^2$  at  $R_2^* = 6.05 \times 10^{-4}$  m<sup>2</sup>K/W; nearly a factor of 1.49 higher, when  $ZT$  is varied from 0.8 to 3.0 (a factor of 3.75). This result indicates that the decrease of  $R_2^*$  has the almost same effect on the device performance as the increase of  $ZT$ . Furthermore, in this calculation range, it is clear that  $q_{\text{max}}$  of TEC is always higher than that of no TEC case.

Fig. 7(b) shows calculation results of the optimized TE leg length ( $L_{\text{opt}}$ ) for each  $q_{\text{max}}$  as a function of  $R_2^*$  and  $ZT$ .  $L_{\text{opt}}$  becomes shorter as  $R_2^*$  and  $ZT$  decreases. For example, at  $R_2^* = 6.05 \times 10^{-4}$  m<sup>2</sup>K/W and  $ZT = 0.8$ , the optimum length of each element becomes approximately 662  $\mu\text{m}$  which is shorter than

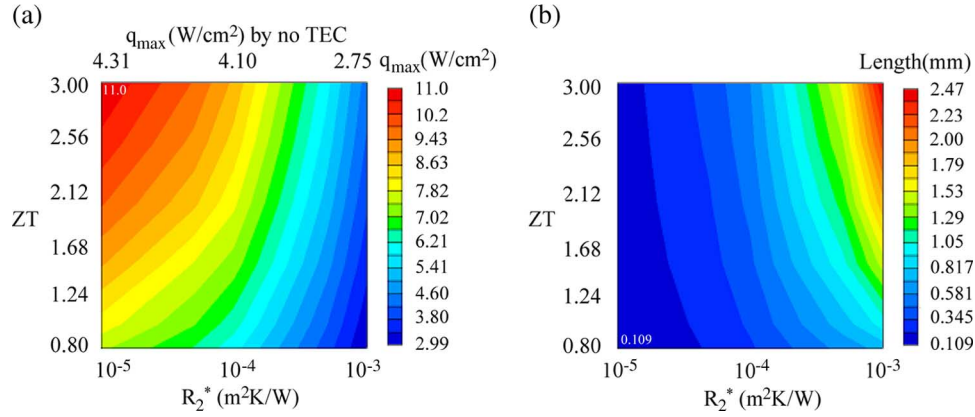


Fig. 7. Effect on  $R_2^*$  and  $ZT$  on  $q_{\max}$  (W/cm $^2$ ) at  $T_{\text{chip}} = 100$  °C and optimum leg length is shown. (a) Contour plot of  $q_{\max}$  (W/cm $^2$ ) at  $T_{\text{chip}} = 100$  °C as a function of  $R_2^*$  and  $ZT$ . (b) Contour plot of optimized leg length for each  $q_{\max}$  as a function of  $R_2^*$  and  $ZT$ .  $R_1^* = 1.73 \times 10^{-3}$  (m $^2$ K/W) is assumed for the calculation.

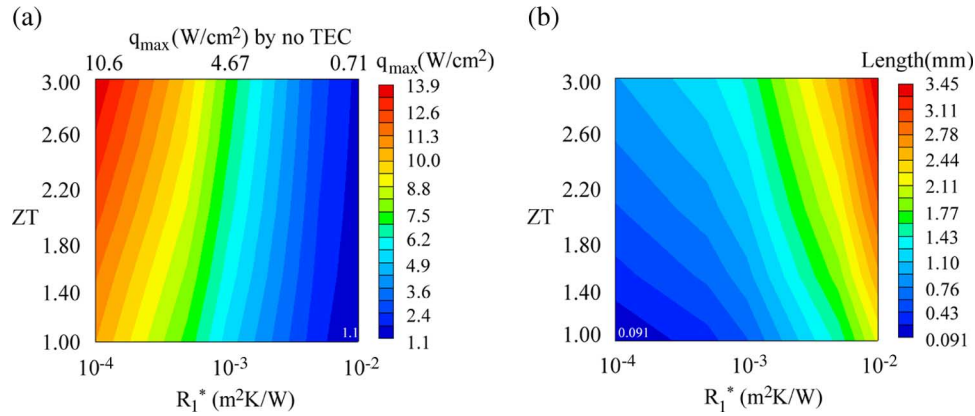


Fig. 8. Effect on  $R_1^*$  and  $ZT$  on  $q_{\max}$  (W/cm $^2$ ) at  $T_{\text{chip}} = 100$  °C and optimum leg length is shown. (a) Contour plot of  $q_{\max}$  as a function of  $R_1^*$  and  $ZT$ . (b) Contour plot of optimized  $L$  for each  $q_{\max}$  as a function of  $R_1^*$  and  $ZT$ .  $R_2^* = 6.05 \times 10^{-4}$  m $^2$ K/W (current technology value) is assumed.

the leg thickness of a commercially available TEC (2–3 mm). Since the TEC with the short leg has a smaller thermal resistance between cold and hot sides, more heat conduction occurs across the TEC. Therefore, a short leg TEC with low  $ZT$  basically needs lower  $R_2$  or  $R_2^*$  to dissipate the high heat flux at the hot end to the ambient air for the better performance.

We also investigated the  $R_1^*$  effect on  $q_{\max}$ . Fig. 8(a) shows a contour plot of  $q_{\max}$  as a function of  $R_1^*$  and  $ZT$ . We fixed  $R_2^* = 6.05 \times 10^{-4}$  m $^2$ K/W (current technology value) and similar calculation to Fig. 7 was carried out. For the purpose of comparison,  $q_{\max}$  calculated from no TEC case is also shown on the top of the graph. One can also see that  $q_{\max}$  is maximized at high  $ZT$  and low  $R_1^*$ . Under our calculation conditions,  $q_{\max}$  for TEC case is always higher than that for no TEC case. When  $R_1^*$  is reduced from  $1.73 \times 10^{-3}$  (current technology value) to  $4.61 \times 10^{-4}$  m $^2$ K/W (a factor of 3.75), the value of  $q_{\max}$  is changed from 3.70 to 7.19 W/cm $^2$  at  $ZT = 0.8$ ; nearly a factor of 1.94 higher. This result indicates that the decrease of  $R_1^*$  is the most effective to enhance the maximum heat dissipation density under our conditions, compared with an increase of  $ZT$  or decrease of  $R_2^*$ . Fig. 8(b) shows calculation results of the optimized TE leg length ( $L_{\text{opt}}$ ) for each  $q_{\max}$  as a function of  $R_1^*$  and  $ZT$ . As similar to Fig. 7(b),  $L_{\text{opt}}$  become shorter at lower  $ZT$  and  $R_1^*$ .

Form these results, it can be said that the TEC with the thin leg length is necessary to increase the TEC performance as the external thermal resistances are improved. However, if the leg length of element ( $L$ ) becomes shorter, the effect of the contact resistance may become significant for the TEC performance because this may induce an additional Joule heating. In the following calculation, the effect of the contact resistance on the maximum heat dissipation density was investigated. In our model, the contact resistance ( $\rho_c/S$ ) can be added to the electrical resistance of the TEC as  $R_e = \rho/G + 2\rho_c/S$  for a simple calculation, assuming that the contact resistance is equally distributed between the hot and cold sides [16]. The factor 2 in the second term of right hand is due to the both sides' contact with the metal electrode. Therefore, the heat dissipation density of TEC module including the effect of the contact resistance can be expressed by

$$q = \frac{Q}{2 \cdot 2NS} = \frac{I^* \alpha \left( T_c \frac{L}{k} - \Delta T \frac{R_2^*}{2} \right) - I^{*2} \cdot \left( \frac{\rho L + 2\rho_c}{2} \right) \left( \frac{L}{k} + \frac{2R_2^*}{2} \right) - (T_a - T_c)}{2 \left( \frac{L}{k} + \frac{R_2^*}{2} \right)} \quad (4)$$

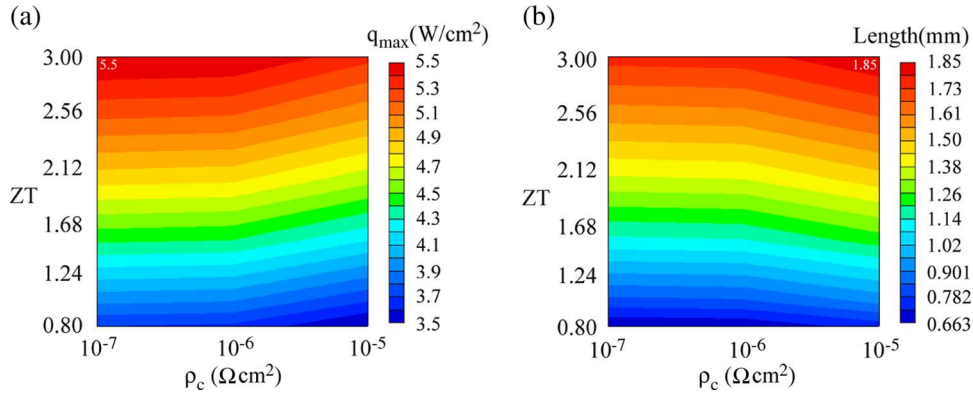


Fig. 9. Effect of  $\rho_c$  and  $ZT$  on  $q_{\max}$  (W/cm<sup>2</sup>) at  $T_{\text{chip}} = 100$  °C and optimum length is shown. (a) Contour plot of  $q_{\max}$  as a function of  $\rho_c$  and  $ZT$ . (b) Contour plot of optimized  $L$  for each  $q_{\max}$  as a function of  $\rho_c$  and  $ZT$ .  $R_1^* = 1.73 \times 10^{-3}$  m<sup>2</sup>K/W and  $R_2^* = 6.05 \times 10^{-4}$  m<sup>2</sup>K/W (current technology values) are assumed for the calculation.

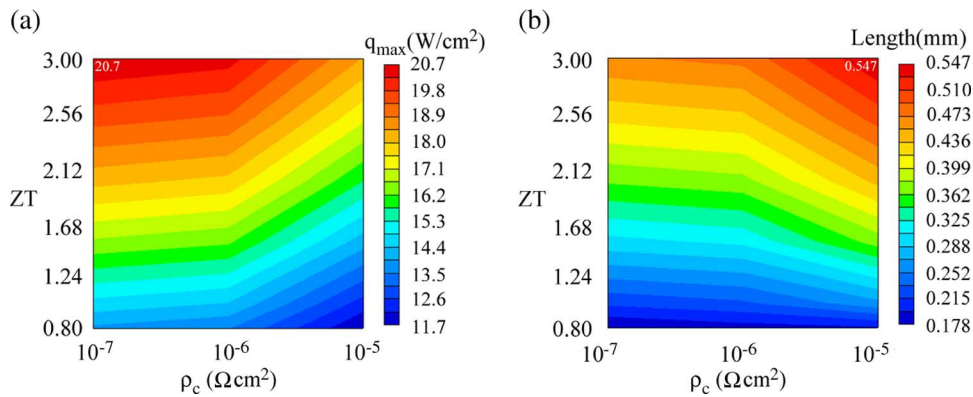


Fig. 10. Effect of  $\rho_c$  and  $ZT$  on  $q_{\max}$  (W/cm<sup>2</sup>) at  $T_{\text{chip}} = 100$  °C and optimum length is shown when  $R_1^*$  and  $R_2^*$  are improved by a factor of 3.75 compared with the current technology values. (a) Contour plot of  $q_{\max}$  as a function of  $\rho_c$  and  $ZT$ . (b) Contour plot of optimized  $L$  for each  $q_{\max}$  as a function of  $\rho_c$  and  $ZT$ .  $R_1^* = 4.61 \times 10^{-3}$  m<sup>2</sup>K/W and  $R_2^* = 1.61 \times 10^{-4}$  m<sup>2</sup>K/W are assumed.

where  $\rho_c$  is the contact resistivity. To investigate the contact resistance effect,  $\rho_c$  was changed in the ranges from 10<sup>-5</sup> to 10<sup>-7</sup> Ωcm<sup>2</sup>, and the similar calculation to Fig. 7 was performed. The calculation results are shown in Fig. 9(a) and (b). Fig. 9(a) shows a contour plot of  $q_{\max}$  at  $T_{\text{chip}} = 100$  °C as a function of  $\rho_c$  and  $ZT$ .  $R_1^* = 1.73 \times 10^{-3}$  (m<sup>2</sup>K/W) and  $R_2^* = 6.05 \times 10^{-4}$  m<sup>2</sup>K/W (current technology values) are assumed for the calculation. When  $\rho_c$  less than 10<sup>-6</sup> Ωcm<sup>2</sup>, the effect of  $\rho_c$  on  $q_{\max}$  is very small (less than 1% reduction compared with no  $\rho_c$  case) because the optimum length is also changed to minimize the additional Joule heating in our calculation as shown in Fig. 9(b). Meanwhile, when  $\rho_c$  approaches to 10<sup>-5</sup> Ωcm<sup>2</sup>, the effect of  $\rho_c$  on  $q_{\max}$  become significant (approximately 6% reduction at  $ZT = 0.8$ ) even if the current and TE leg length are optimized. Therefore, it can be concluded that the contact resistivity should be reduced less than 10<sup>-6</sup> Ωcm<sup>2</sup> to avoid the significant reduction of  $q_{\max}$  in the current packaging technology. Fig. 9(b) shows the contour plot of the optimum leg length as a function of  $\rho_c$  and  $ZT$ . One can see that the optimum leg length decreases when  $\rho_c$  is larger, which is due to the avoidance of the excess additional Joule heating.

Finally, the effect of  $\rho_c$  on  $q_{\max}$  was investigated when both  $R_1^*$  and  $R_2^*$  are improved by a factor of 3.75 compared with the current technology values. Fig. 10(a) shows a contour plot of  $q_{\max}$  at  $T_{\text{chip}} = 100$  °C as a function of  $\rho_c$  and  $ZT$  at

$R_1^* = 4.61 \times 10^{-3}$  m<sup>2</sup>K/W and  $R_2^* = 1.61 \times 10^{-4}$  m<sup>2</sup>K/W. As similar to Fig. 9(a), it can be seen that  $q_{\max}$  is not so sensitive to  $\rho_c$  when  $\rho_c$  is less than 10<sup>-6</sup> Ωcm<sup>2</sup> (less than 3% reduction compared with no  $\rho_c$  case). However,  $q_{\max}$  is reduced by 11%~16% in comparison with the case without contact resistance at  $ZT = 0.8 \sim 3.0$  when  $\rho_c$  reaches to 10<sup>-5</sup> Ωcm<sup>2</sup>. Therefore, it is clear that the reduction of the contact resistance becomes important as the external thermal resistances are improved. A contour plot of optimum leg length as a function of  $\rho_c$  and  $ZT$  is shown Fig. 10(b). One can clearly see that the optimum leg length shown in Fig. 10(b) is much shorter that shown in Fig. 9(b). Therefore, it can be said that the reason why the contact resistance gives the significant effect to  $q_{\max}$  when the external thermal resistance is improved is due to lower optimum leg length. As similar to the conclusion from Fig. 9, it is very important that the contact resistivity is reduced less than 10<sup>-6</sup> Ωcm<sup>2</sup> to avoid additional Joule heating effect even if the external thermal resistance is improved.

#### IV. CONCLUSION

The BiTe-based TEC integrated with an IC and heat sink was analyzed by the 1-D equivalent circuit model. When the thermal resistance between the hot side of a TEC and ambient temperature ( $R_2$ ), is not negligible compared with the thermal resistance



of the TE element ( $R_{th}$ ), our calculation shows the current optimization considering  $R_2$  is very effective to maximize the TEC performance. Furthermore, if we can optimize the geometrical factor ( $G$ ) as well as  $I$  considering  $R_2$  at a given heat dissipation, optimally designed TE modules calculated by our model can increase the chip operation power by at least 15% in comparison with the case without a TEC while maintaining the chip temperature below 100 °C. Therefore, it can be concluded that the optimization of  $G$  and  $I$  considering the external thermal resistance at a given  $Q$  has significant impact on a TEC's performance to reduce  $T_{chip}$ . With existing package level thermal resistance ( $R_1 = 0.571$  K/W and  $R_2 = 0.200$  K/W), optimum TE module length is 0.612–1.76 mm and maximum heat dissipation density should be 3.70–5.52 W/cm<sup>2</sup> with a ZT of 0.8–3.0. There is 13.3% to 41.9% improvement compared to no TEC case. By improving external thermal resistances, TE modules with a thinner leg length and higher  $ZT$  can increase the heat dissipation density. The effect of the contact resistance on the power dissipation density was investigated. The reduction of the power dissipation density was less than 3.0% compared to no contact resistance model when the contact resistivity is less than  $10^{-6}$  Ωcm<sup>2</sup> even if the external thermal resistance is improved.

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